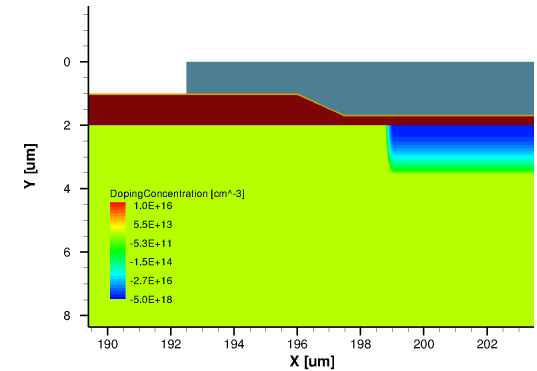
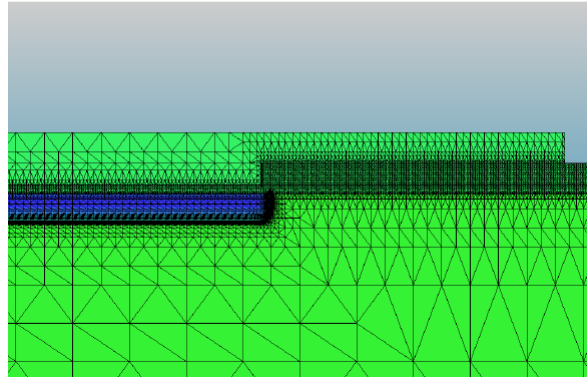
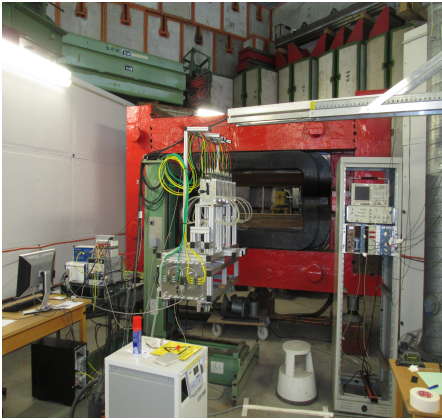


# The CMS Phase-II Tracker Upgrade

## Testbeam Telescopes

## TCAD Simulations



Thomas Eichhorn  
DESY Student Seminar on  
Detector Development  
23.05.2013

## ➤ Introduction

- The CMS Phase-II Tracker Upgrade
- The DESY-II Testbeam & Pixel Telescopes
- Sensor Simulations
- Quick Reminder: Physics of Silicon Sensors

## ➤ Simulation Results

- Sensor Properties in Simulations
- Modeling Radiation Damage

## ➤ Characterising the DESY-II Testbeam

## ➤ Summary and Outlook

# The CMS Phase-II Tracker Upgrade



## > Current tracker design:

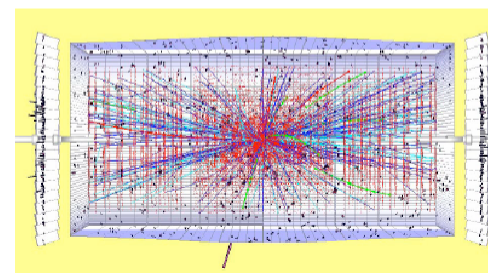
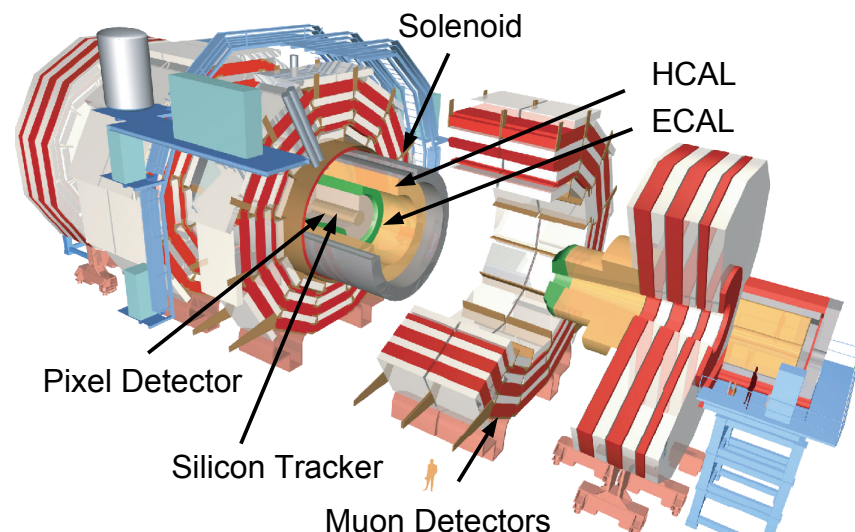
- Built for 10 year run time ( $500 \text{ fb}^{-1}$ )
- Peak instantaneous luminosity of  $10^{34} \text{ cm}^{-2}\text{s}^{-1}$

## > High luminosity upgrade in 202X:

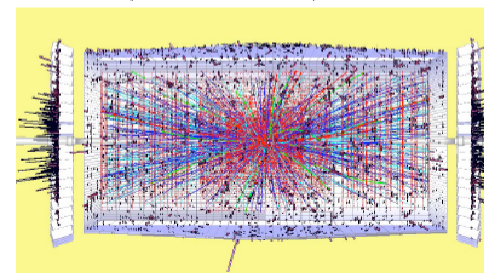
- Increase luminosity by a factor of 5  $\rightarrow$  higher occupancy
- Even harsher radiation environment

## > Upgraded CMS strip tracker requirements:

- Increase granularity to maintain low detector occupancy
- Tracker to contribute to the CMS level-1 trigger
- Radiation hard sensors



LHC,  $L = 10^{34} \text{ cm}^{-2}\text{s}^{-1}$ ,  $\sim 20 \text{ MBE}$



SLHC,  $L = 10^{35} \text{ cm}^{-2}\text{s}^{-1}$ ,  $\sim 200 \text{ MBE}$

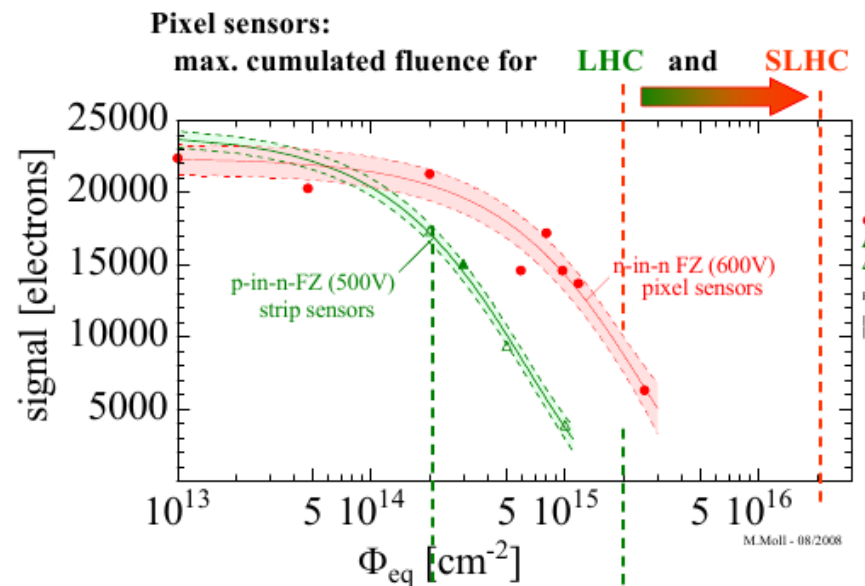
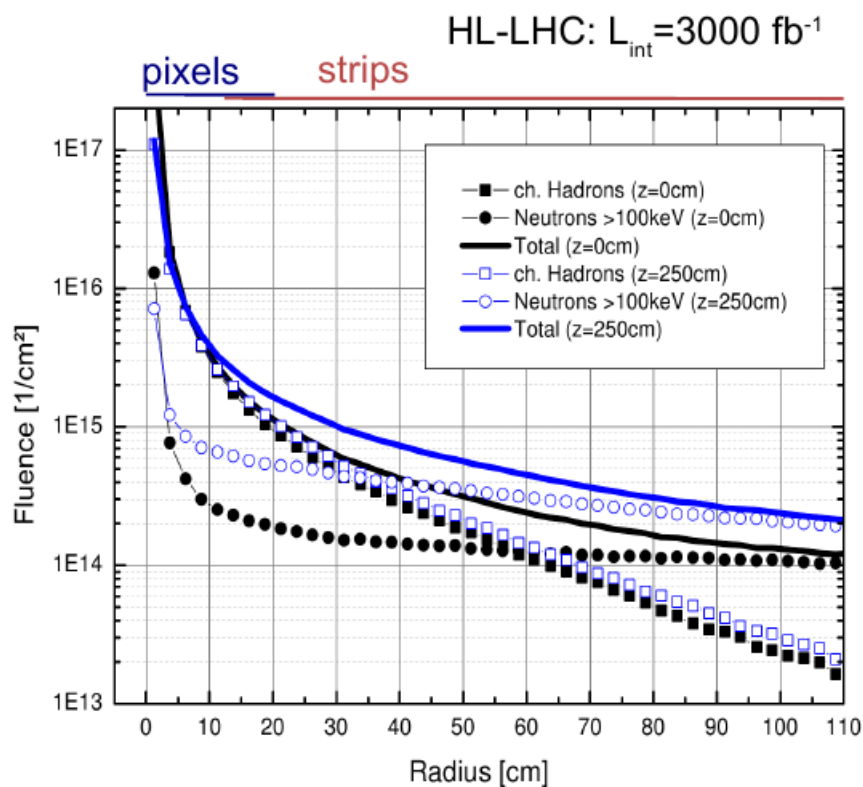


# The CMS Phase-II Tracker Upgrade



➤ Signal degradation for currently installed sensors

➤ Mix of irradiations expected



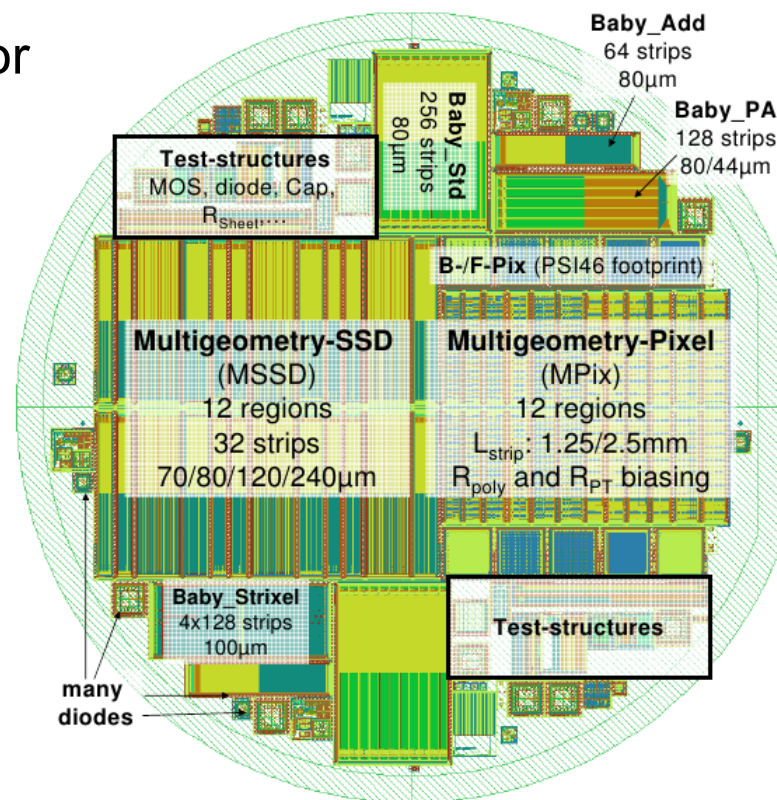
Strip sensors:  
max. cumulated fluence for LHC and SLHC

➤ Detailed and comprehensive studies of possible future sensor materials and technologies needed

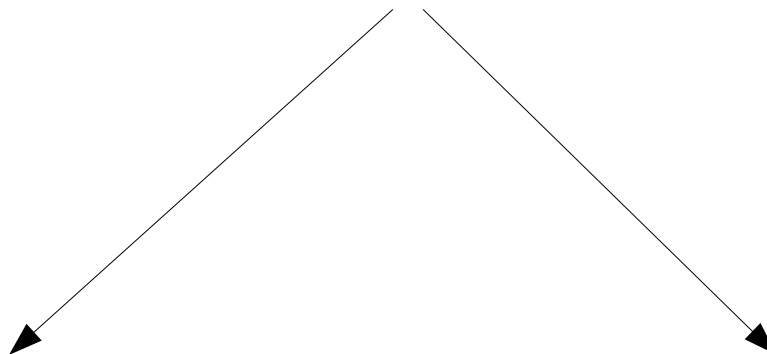




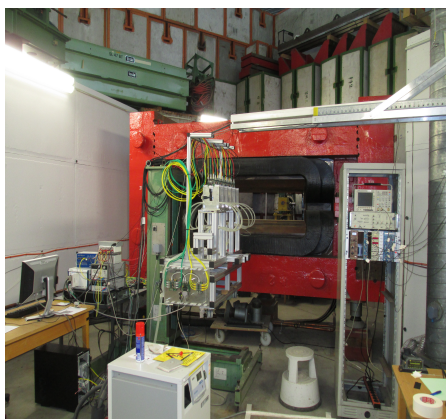
- Goal: identify the technological baseline for the CMS Phase-II strip tracker upgrade
- Single high-quality wafer manufacturer
- Dedicated structures for measurement of specific sensor properties
- Common testing procedures for comparability
- Points under investigation:
  - Radiation damage effects
  - Annealing behaviour
  - Evaluate geometries and materials



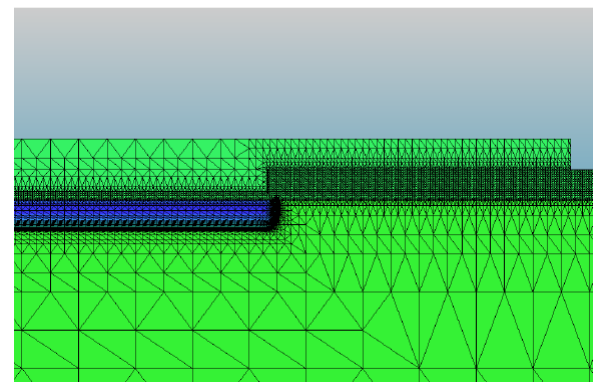
➤ Tools for sensor development



➤ Testbeam measurements



➤ TCAD sensor simulations

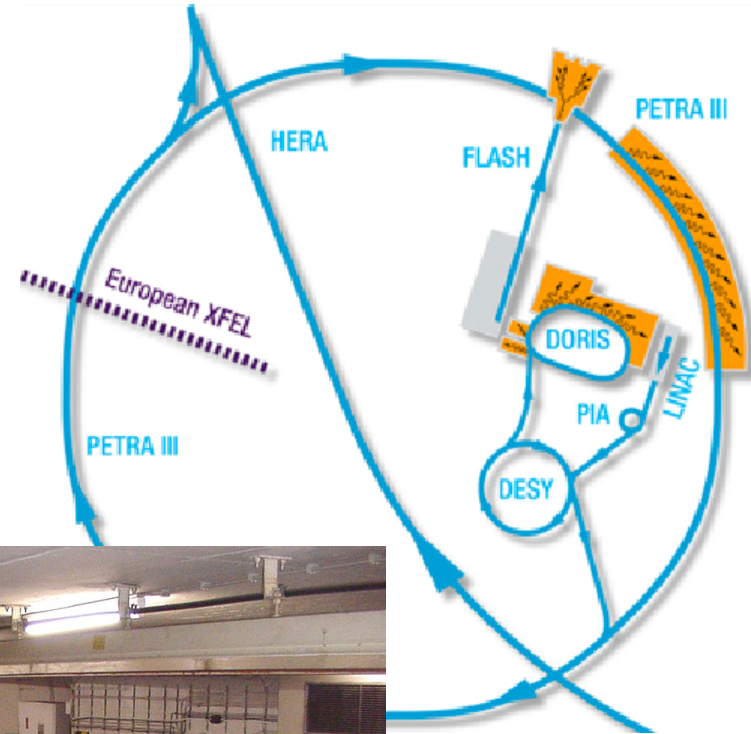
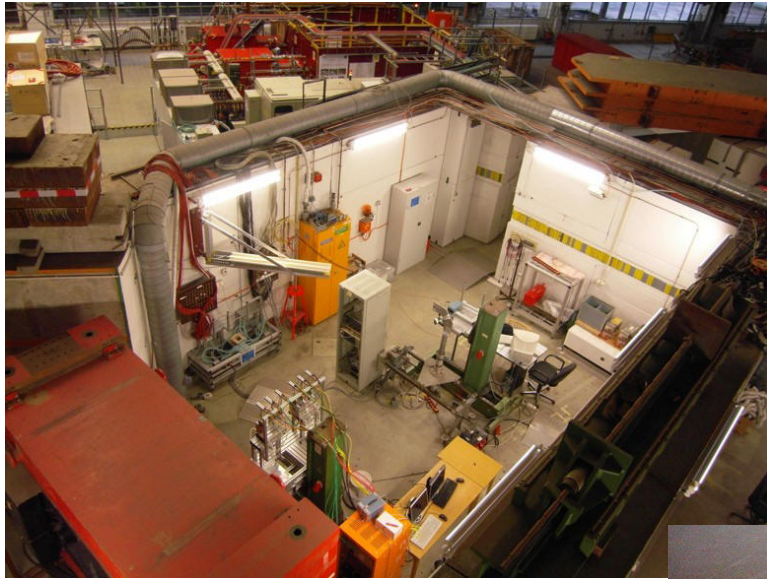


➤ Tools for sensor development

➤ Testbeam measurements

➤ TCAD sensor simulations

# The DESY-II Testbeam

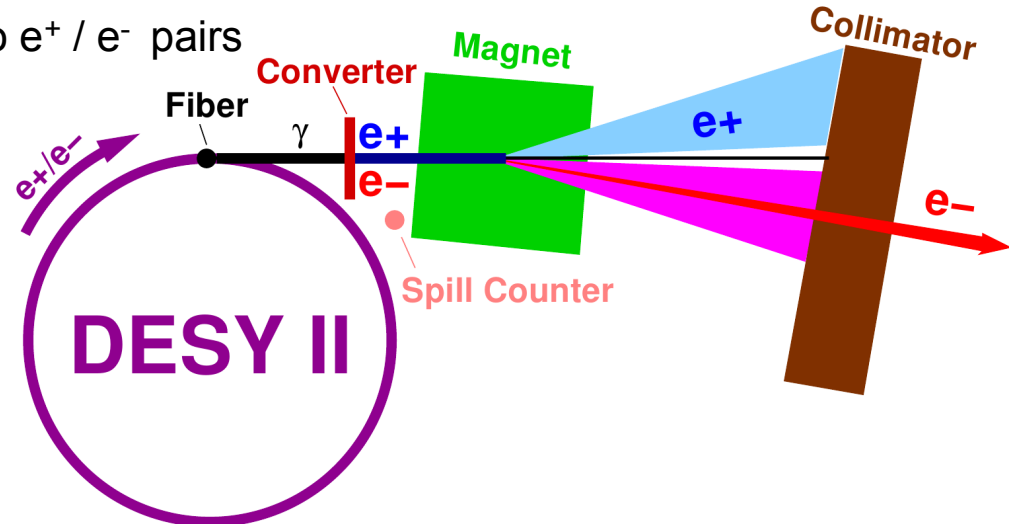


- DESY-II synchrotron
- Pre-accelerator
  - HERA (2007)
  - DORIS (2012)
  - PETRA
- 3 testbeam lines



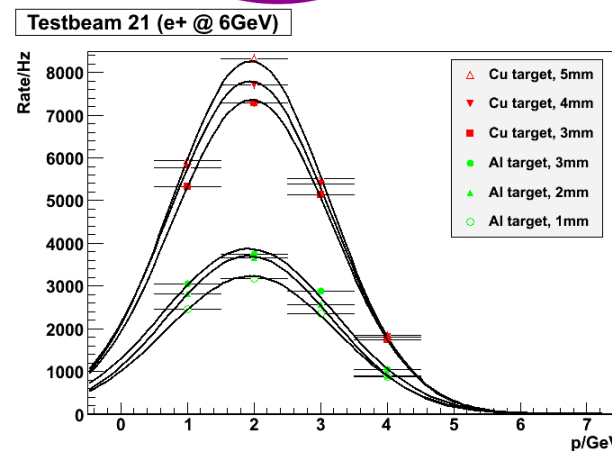
## > Testbeam from DESY-II synchrotron

- Carbon fiber generates a bremsstrahlung beam
- Metal target plate converts photons to  $e^+$  /  $e^-$  pairs
- Dipole magnet spreads out beam
- End collimator cuts out final beam



## > Beam momentum

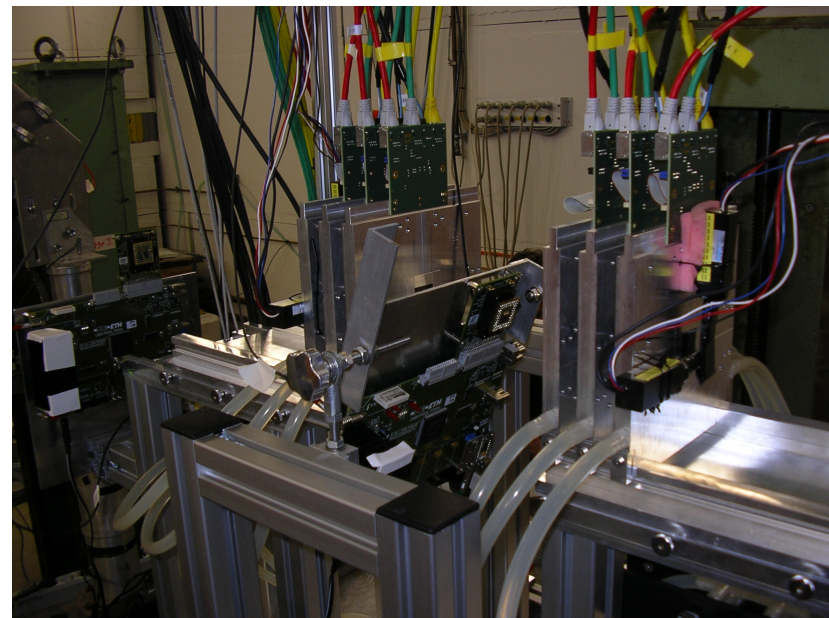
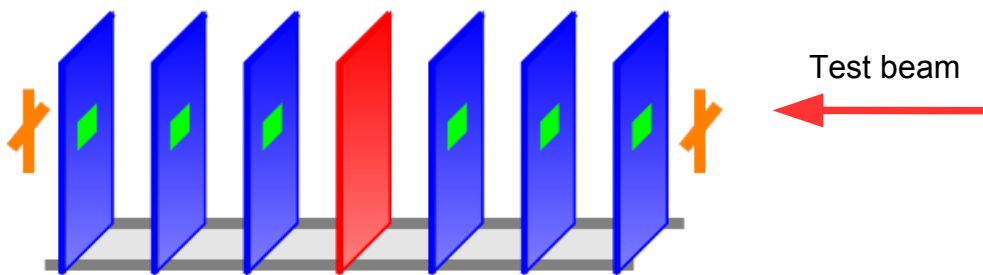
- Changing magnet current allows energies from 1 to 6 GeV
- Low energies require very thin sensors to reduce multiple scattering





## ➤ What is a beam telescope?

- Series of parallel silicon sensor planes inserted into a particle test beam
- Reconstruct particle tracks through the sensor planes wrt. time and position
- Use gained reference information to evaluate *device under test* (DUT) performance
- Contribution towards the development of future detector systems
- High precision and fast read-out speed needed

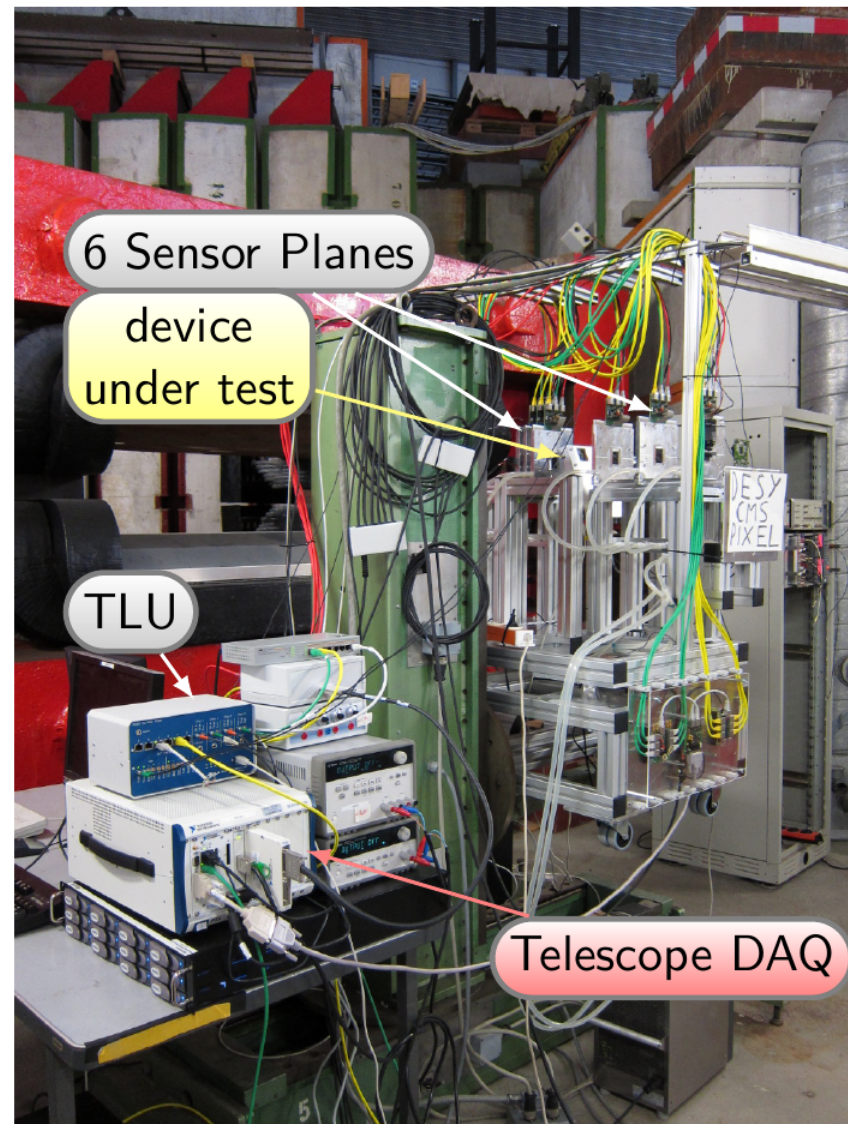




## ➤ Datura telescope at DESY:

- 6 sensor planes
  - Monolithic Active Pixel Sensor
  - Rolling-shutter read-out
  - $t \sim 115 \mu\text{s}$
- Flexible mechanics & cooling
- Trigger logic unit (TLU)
  - Easy integration of DUTs
- NI PXIe Telescope DAQ
- Data analysis with EUTelescope

## ➤ Table-top particle physics experiment!



➤ Tools for sensor development

➤ Testbeam measurements

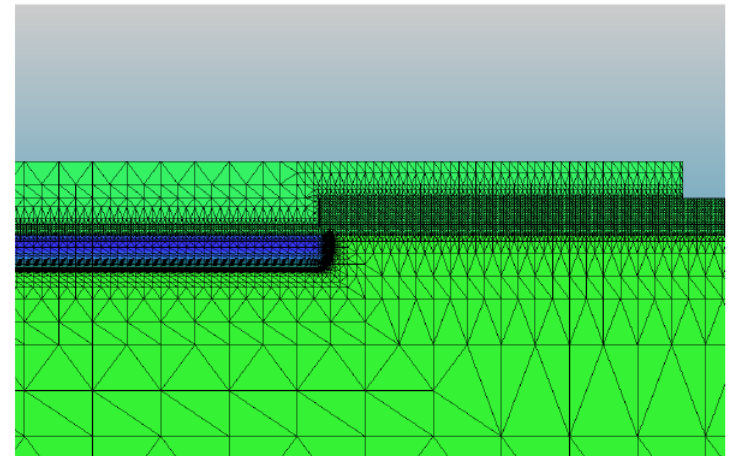
➤ TCAD sensor simulations

## > Technology Computer Aided Design

- Commercial software for semiconductor simulations
- Many applications, extensive use in semiconductor industry
- Two main packages: *Silvaco Atlas*, *Synopsys Sentaurus*

## > Standard FEA Framework:

- Create 2D or 3D structure with materials, doping, etc and generate a mesh
- Select physical models to be used in simulation:
  - > temperature
  - > field generation
  - > carrier recombination
  - > trapping (→ radiation damage)
  - > carrier lifetime
  - > ...



## ➤ Standard FEA Framework:

- Include external effects: electric circuit (SPICE), laser illumination, traversing particle...
- Specify what kind of simulation: simple I-V, capacitive, or time-dependant
- Run simulation: at each mesh-point solve

### ➤ poisson's equation

$$\frac{d^2 V(\mathbf{x})}{dx^2} = -\frac{\rho(\mathbf{x})}{\epsilon_r \epsilon_0}$$

### ➤ carrier continuity equations:

$$\nabla \cdot \vec{J}_n = q \cdot (R_{\text{eff}} + \frac{\partial n}{\partial t}) \quad -\nabla \cdot \vec{J}_p = q \cdot (R_{\text{eff}} + \frac{\partial p}{\partial t})$$

- Derive physical properties:

### ➤ electric field

### ➤ current flows

### ➤ charge distributions

### ➤ ...

## ➤ Working group to streamline and coordinate tasks

### ▪ 5 institutes:

- Delhi University (India)
- DESY (Germany)
- Karlsruhe Institute of Technology (Germany)
- Helsinki Institute of Physics (Finland)
- University of Pisa (Italy)



## ➤ Group aims:

- Provide input to the CMS sensor design
- Points under investigation:
  - Device design – simulate capacitances, verify isolation techniques
  - Charge collection and read-out, research optimal layout
  - Radiation damage → derive a trap model
  - Comparison of simulation tools

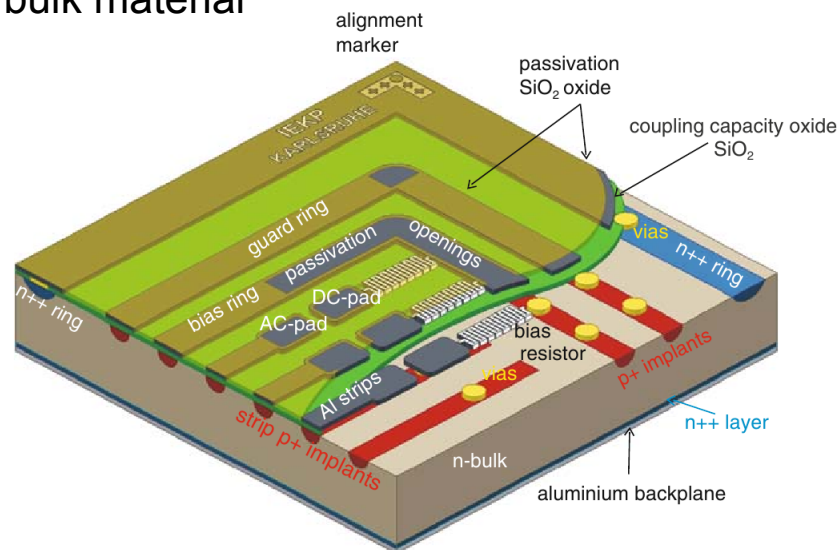
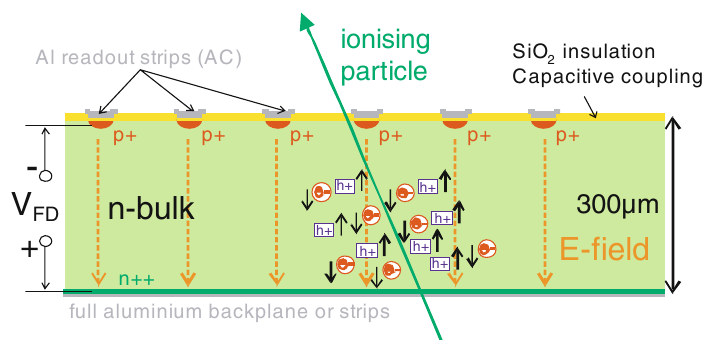


➤ How does a silicon sensor work?



## ➤ Material & structure:

- Boron or phosphorous impurities in silicon → 'doping'
- p/n junction between strip implantation and bulk material
- $\text{SiO}_2$  insulation for capacitive coupling



## ➤ Operation:

- Bias voltage applied to deplete sensor of free charge carriers → creates electric field
- Traversing ionising particle generates e-/h pairs
- Charge collected at segmented read-out strips

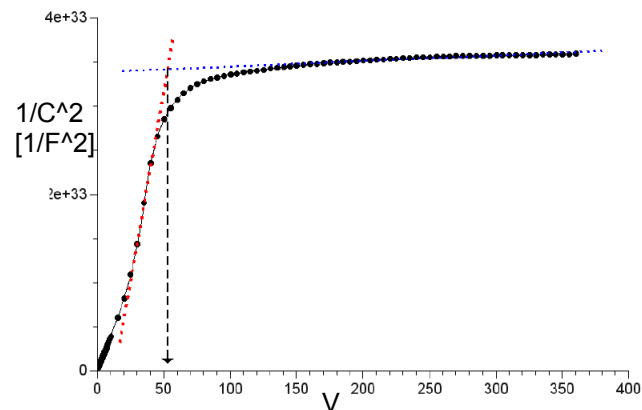
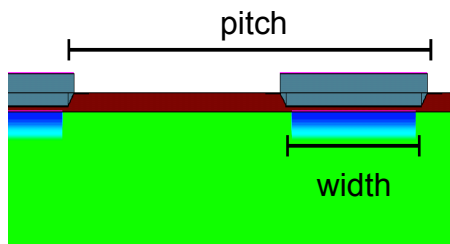
## > Depletion voltage

- Voltage needed to deplete sensor of free charge carriers
- Extracted from capacitance – voltage measurements

$$V_d \approx \frac{e \cdot d^2}{2 \cdot \epsilon_r \epsilon_0} \cdot |N_{\text{eff}}|$$

## > Strip width and pitch

- Pitch: distance between strips
- Strip noise  $\sim w/p$  ratio



## > AC/DC coupling

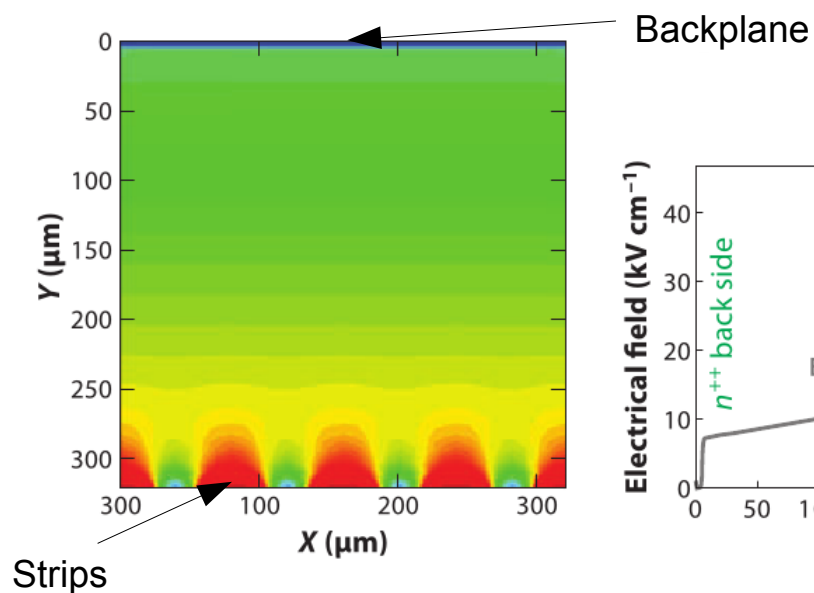
- DC: sensor connected directly to read-out chip  $\rightarrow$  pixel detectors
- AC: capacitive coupling via an oxide  $\rightarrow$  strip detectors

## > p-in-n or n-in-p?

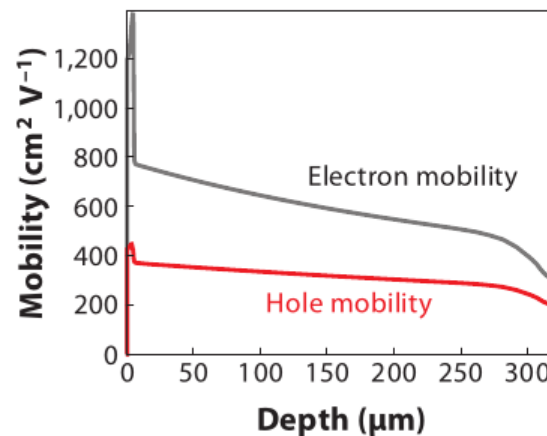
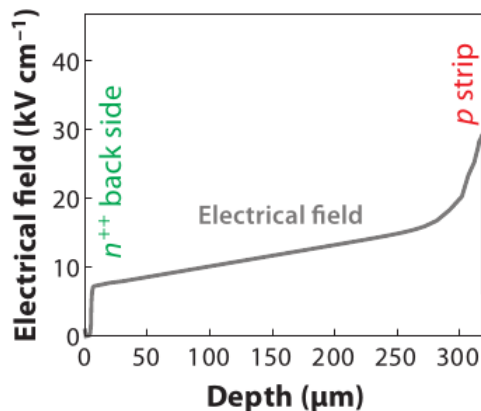
- p-in-n  $\rightarrow$  collects holes
- n-in-p  $\rightarrow$  collects electrons

## ➤ Example: traversing minimally ionising particle (*MIP*)

→ generating  $\sim 108$  e/h pairs /  $\mu\text{m Si}$



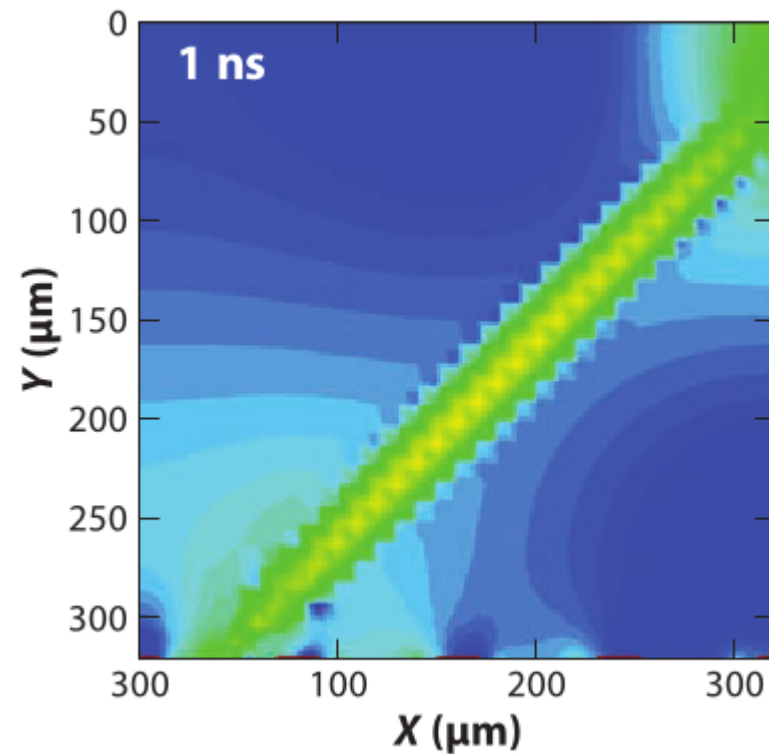
Electric field



Carrier mobility

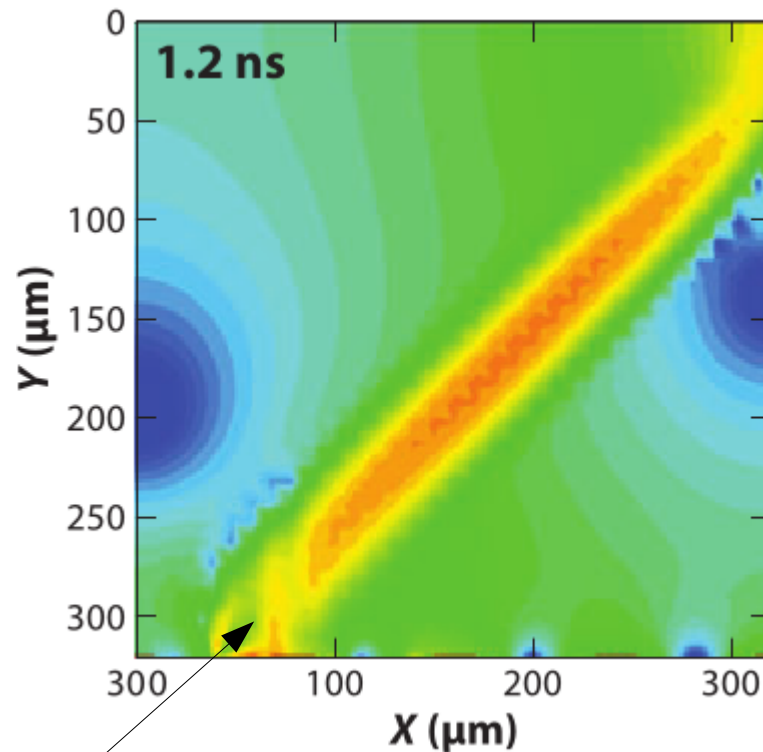
- Particle generates electron / hole pairs

- Charge densities



- Particle generates electron / hole pairs

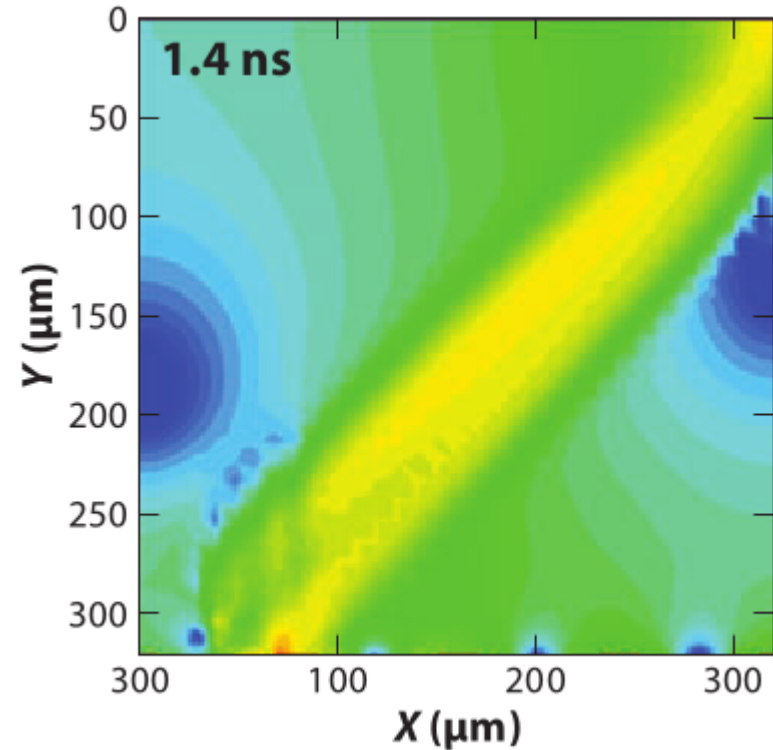
- Charge densities



Holes collected at sensor strips

- Electric field separates charge carriers
- Electrons drift to backplane
- Holes collected at strips

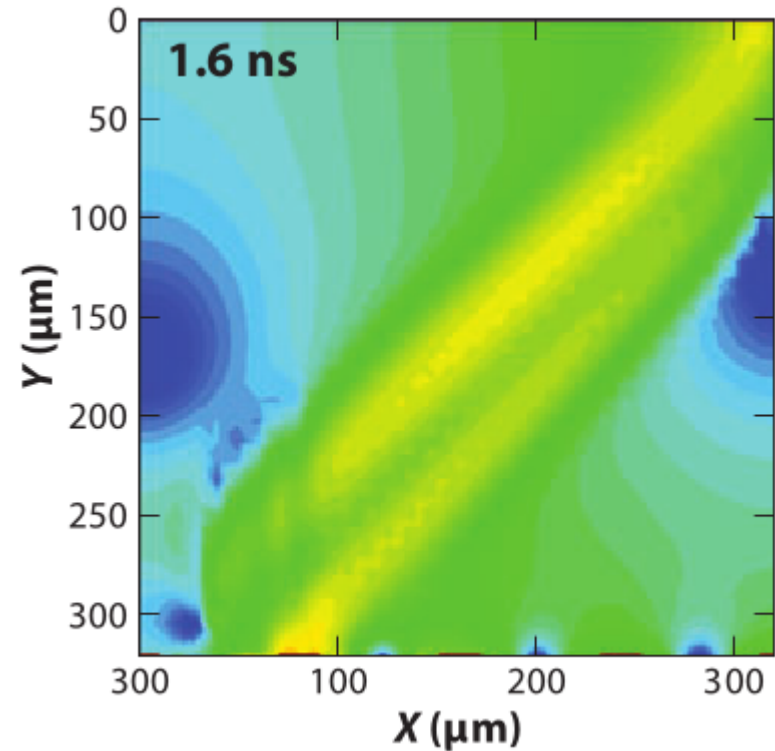
## ➤ Charge densities





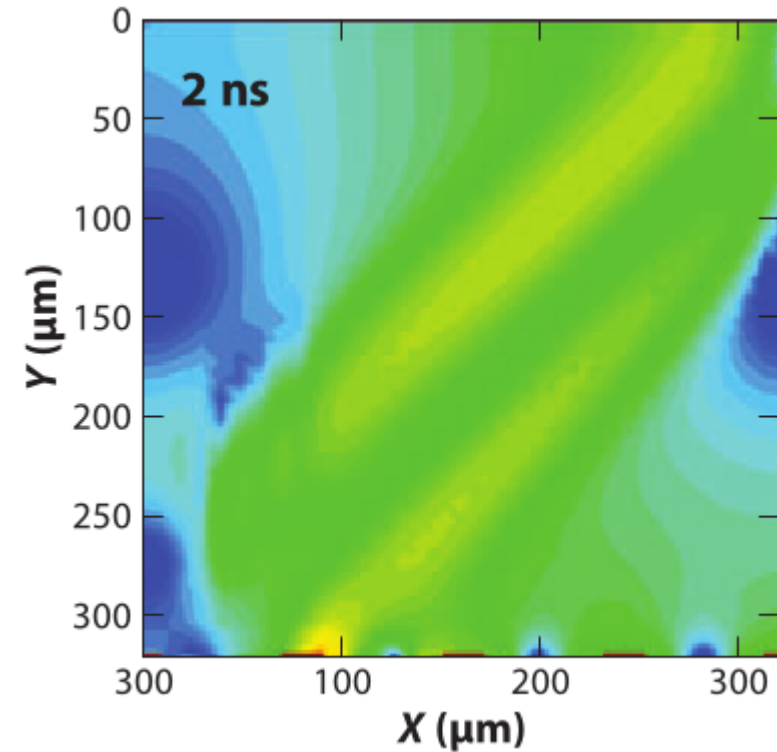
- Electric field separates charge carriers
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➤ Charge densities



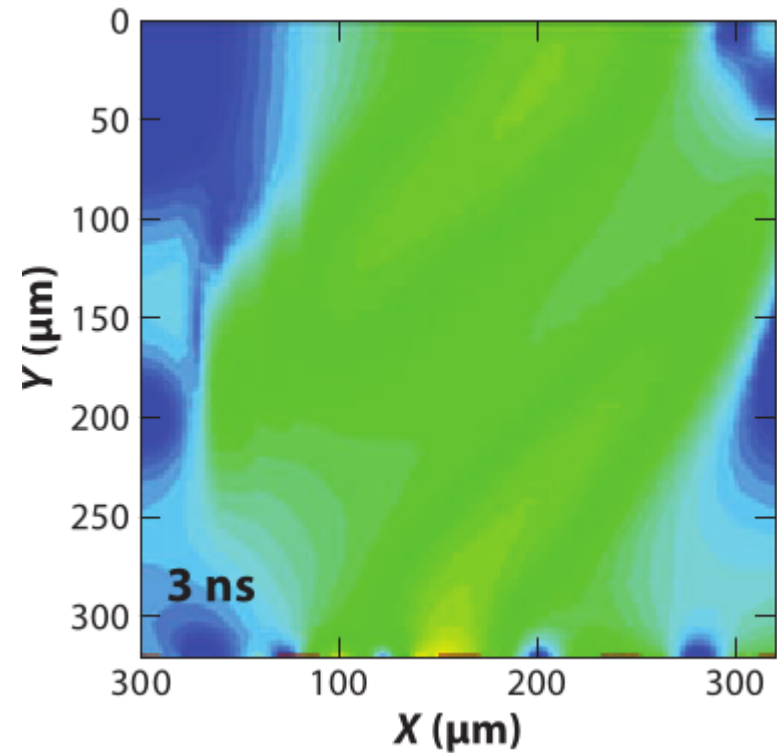
- Electric field separates charge carriers
- Electrons drift to backplane
- Holes collected at strips

## ➤ Charge densities



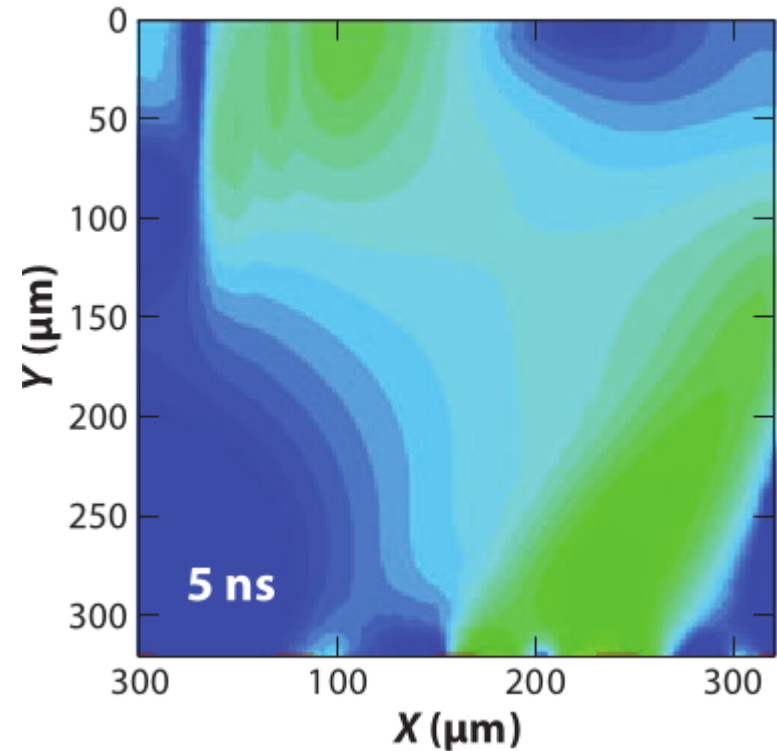
- Electric field separates charge carriers
- Electrons drift to backplane
- Holes collected at strips

## ➤ Charge densities



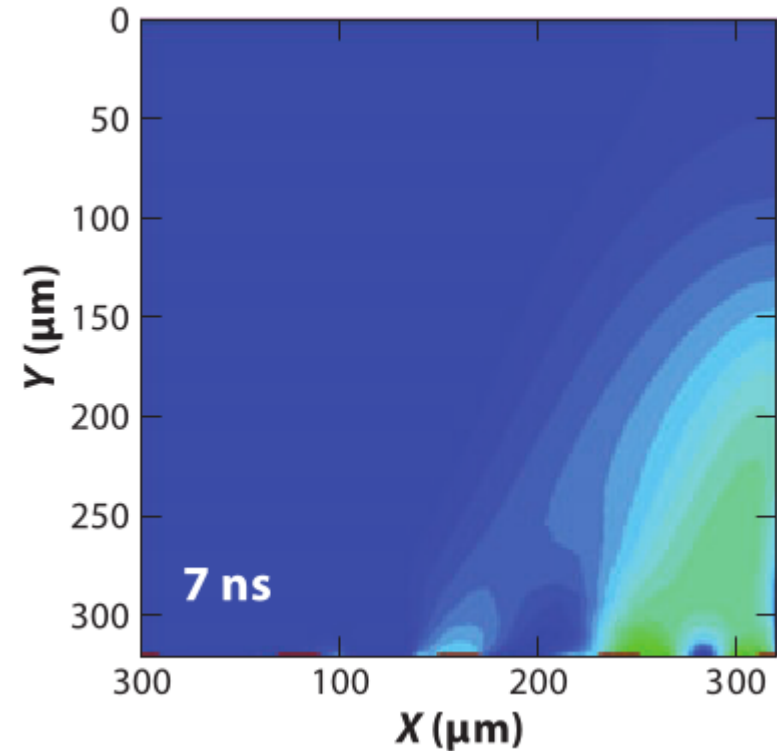
- Electric field separates charge carriers
- Electrons drift to backplane
- Holes collected at strips
- $\mu_e > \mu_h \rightarrow$  electrons faster

## ➤ Charge densities



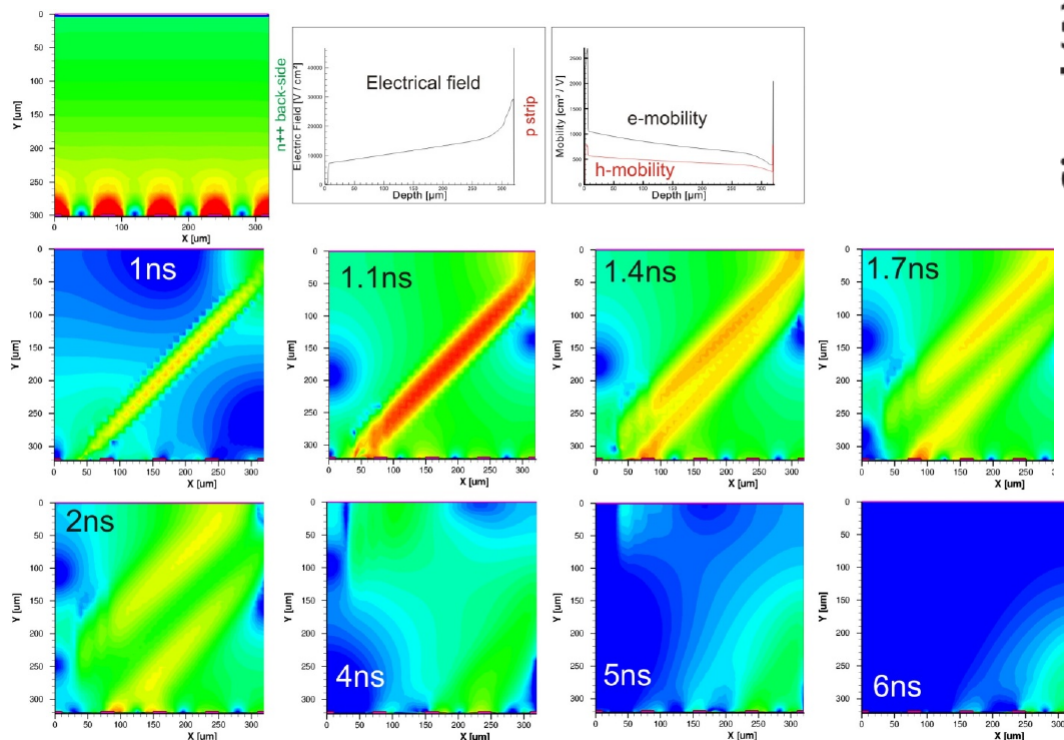
- Electric field separates charge carriers
- Electrons drift to backplane
- Holes collected at strips
- $\mu_e > \mu_h \rightarrow$  electrons faster

## ➤ Charge densities

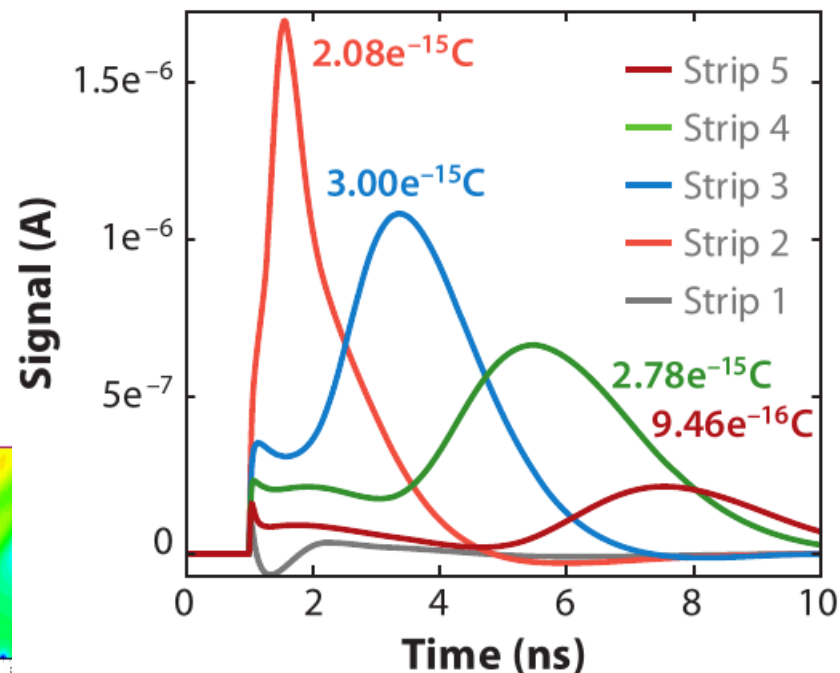


➤ Recieved signals

➤ Inner strips collect most charge



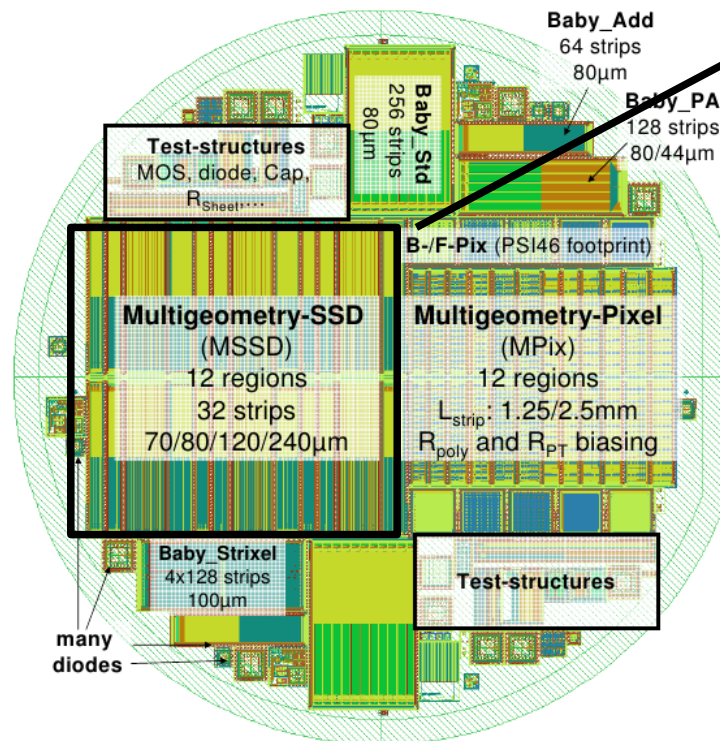
➤ Collected charge over time





## ➤ MSSD sensors (Multi-geometry silicon strip detectors):

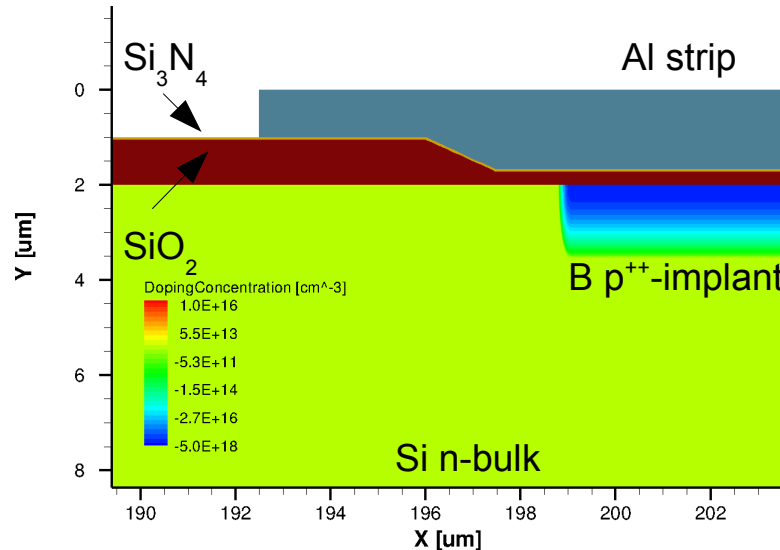
- 12 regions on wafer, 32 strips each, with 70 / 80 / 120 / 240  $\mu\text{m}$  pitch
- Main source of strip noise: inter-strip capacitance  $C_{\text{int}}$
- Can measurements be verified by simulations?



Sensor	Pitch [ $\mu\text{m}$ ]	Implant width [ $\mu\text{m}$ ]	Alu width [ $\mu\text{m}$ ]	w/p
1	120	18	26	0.15
2	240	36	44	0.15
3	80	12	20	0.15
4	70	10.5	18.5	0.15
5	120	30	38	0.25
6	240	60	68	0.25
7	80	20	28	0.25
8	70	17.5	25.5	0.25
9	120	42	50	0.35
10	240	84	92	0.35
11	80	28	36	0.35
12	70	24.5	32.5	0.35

## ➤ Not all sensor parameters known or released by manufacturer

- Doping profile, concentration and depth, oxide thickness, etc.



- Include diagonal aluminium strip component to model etching
- 50 nm Si<sub>3</sub>N<sub>4</sub> layer
- 270 – 680 nm SiO<sub>2</sub>
- Implant depth depends on type (pnn/npp) and sensor thickness (120 / 200 / 320 μm)
- p-spray isolation concentration 1e16 cm<sup>-3</sup>

## ➤ Compare simulations with measurements to get these parameters

- Approximate simulated structure to the actual sensor geometry
- How do these parameters influence sensor properties?

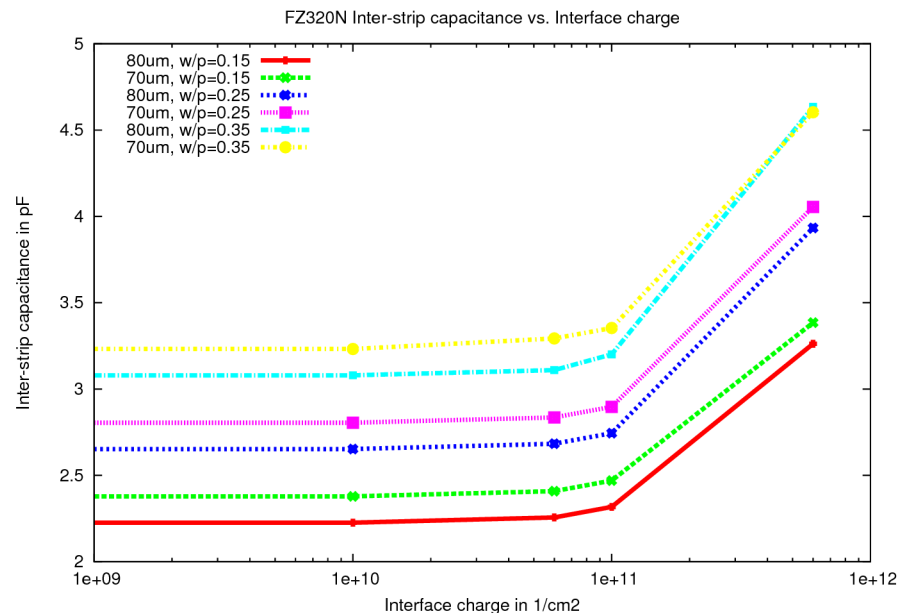
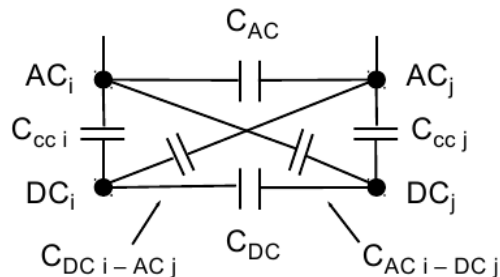
## ➤ Simulations can visualise how parameters influence sensor properties

- Interface charge  $Q_f$  increases  $C_{int}$
- Resulting changes to electric field

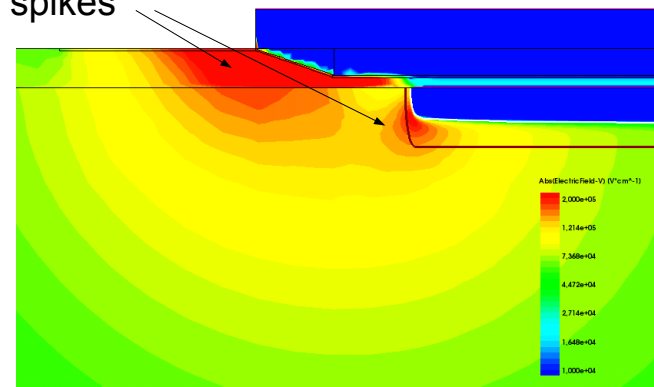
## ➤ Some discrepancies to reality

- Simulation requires 'additional' capacitances in the calculation:

$$C_{int} = C_{AC} + C_{DC} + 2 * C_{ACDC}$$



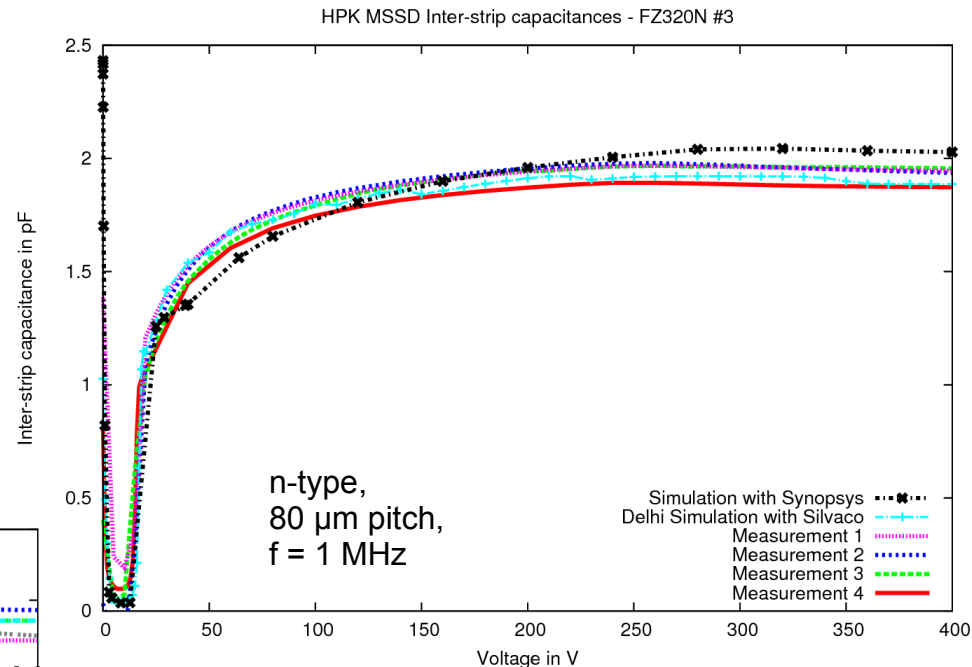
field 'spikes'



# Comparison with Measurements

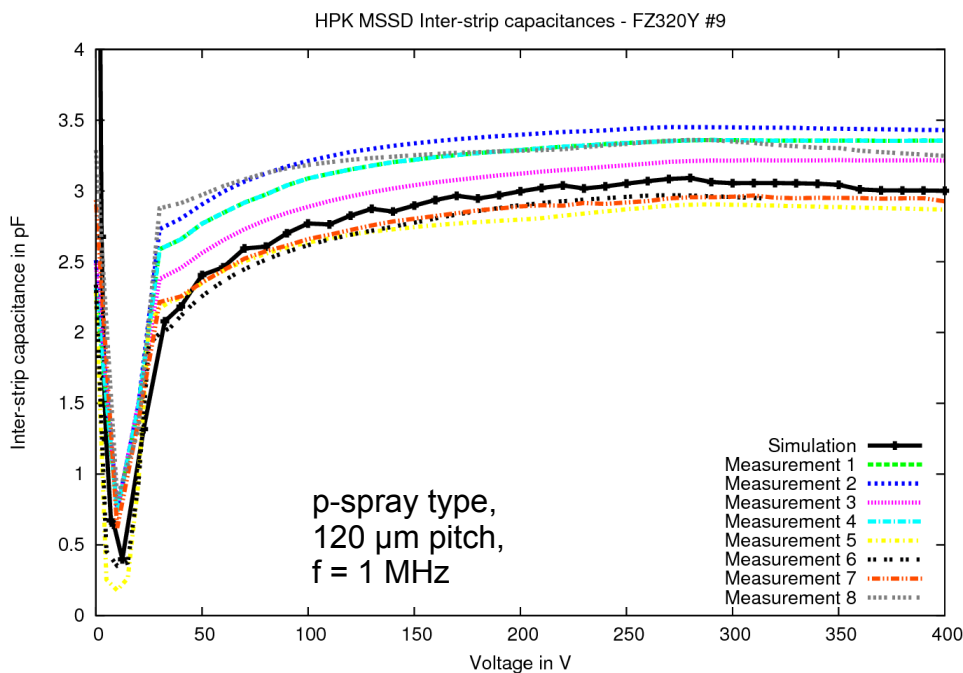


- Simulated  $C_{\text{int}}$  in good agreement with measurements for all materials and geometries
- Both main simulation packages give comparable results

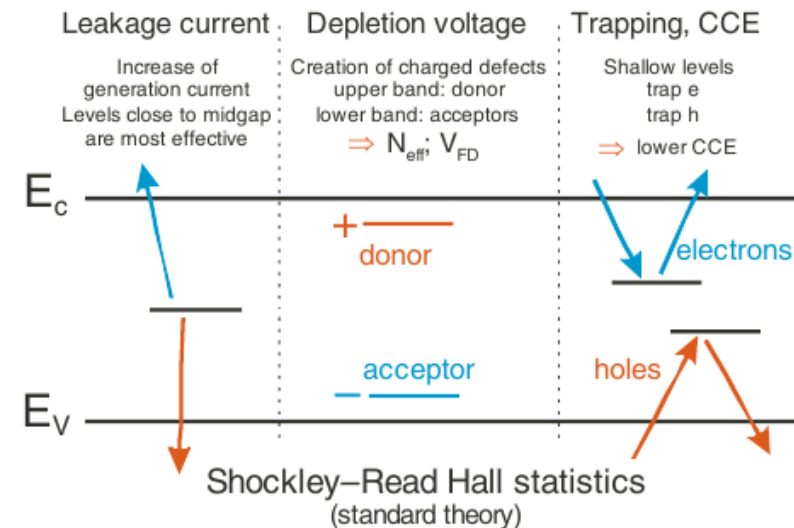
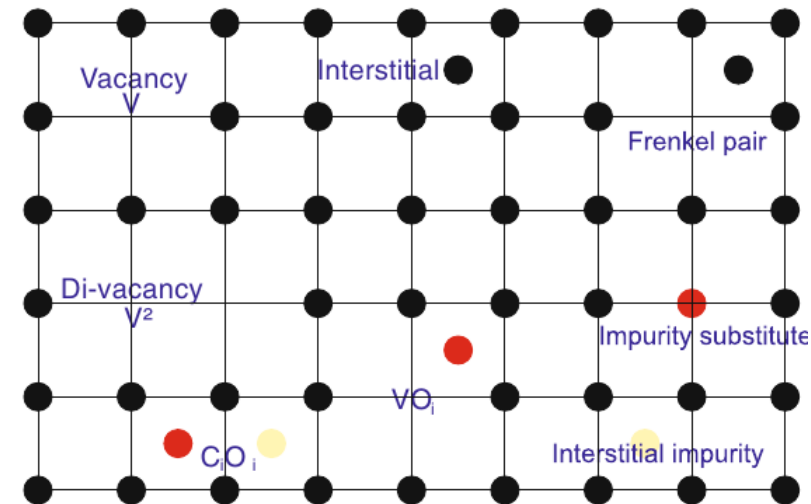


- Measurement spread due to different wafers and institutes

→ Minor variations in temperature and relative humidity



- Radiation damage creates point- and cluster defects
- Influence on sensor properties through states in the Si band-gap
  - Increase in leakage current
  - Change in depletion voltage
  - Reduction of charge collection efficiency by trapping
- Defect types and concentrations depend on material and radiation type (ch. hadron, neutron, gamma irradiation)



## ➤ Implemented into simulations by including traps

- Energy states in the silicon band-gap
- Characterised by:
  - Energy
  - Concentration
  - Capture cross-section for electrons and holes
- Various existing models for different materials and irradiations
- Search for a trap model that fits best to measured data
- CMS Simulation Group has used the *EVL-4* model by V. Eremin to cross-check simulations

## ➤ Preliminary trap model

- Simulate the double-peak electric field observed in irradiated sensors
- Defects approximated into two 'effective' traps

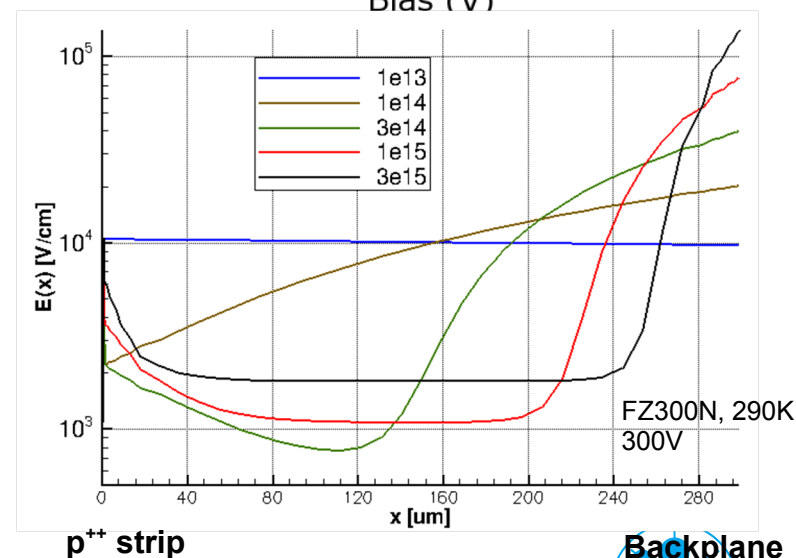
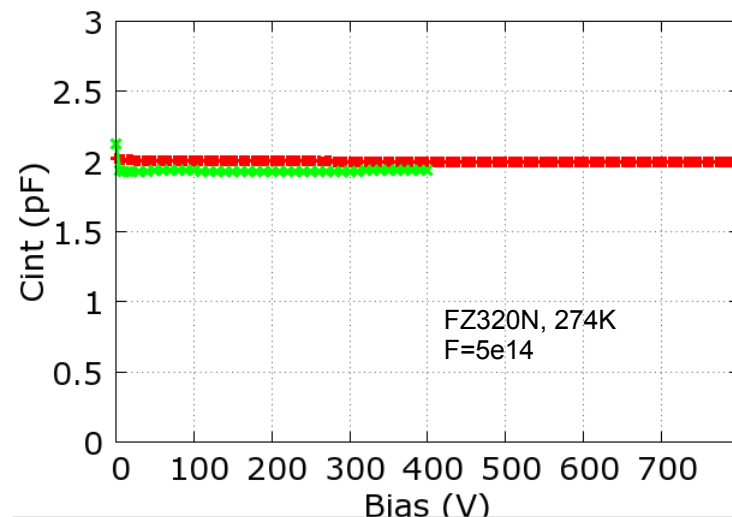
Defect	Energy [eV]	$\sigma_n$ [cm <sup>-2</sup> ]	$\sigma_p$ [cm <sup>-2</sup> ]	g [cm]
Acceptor	$E_c - 0.525$	4e-14	4e-14	0.8
Donor	$E_v + 0.48$	4e-14	4e-14	0.8

## ➤ First tests: basic 2-trap model can reproduce some measurements

- Interstrip Capacitance
- Double-peak in electric field
  - Trapped charge carriers contribute to field

## ➤ Ongoing work:

- Compare other sensor properties after irradiation with measurements
- Other trap models currently being tested to include further defects
- Ongoing search for a trap model describing all effects



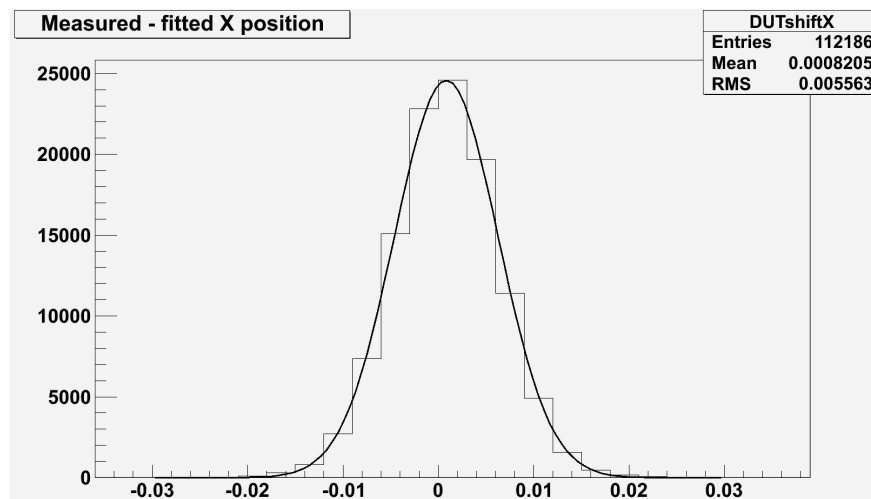
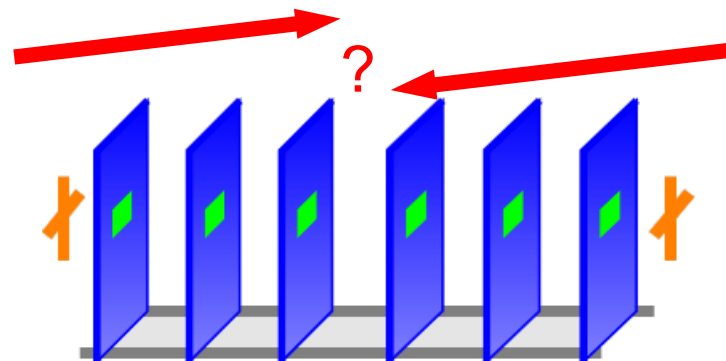
➤ Tools for sensor development

➤ Testbeam measurements

➤ TCAD sensor simulations



- Goal: use the testbeam to evaluate performance of future sensors
- Prerequisite: measure beam properties and telescope capabilities
- Telescope figure of merit: intrinsic tracking resolution
- Use each telescope plane as a DUT for residuals



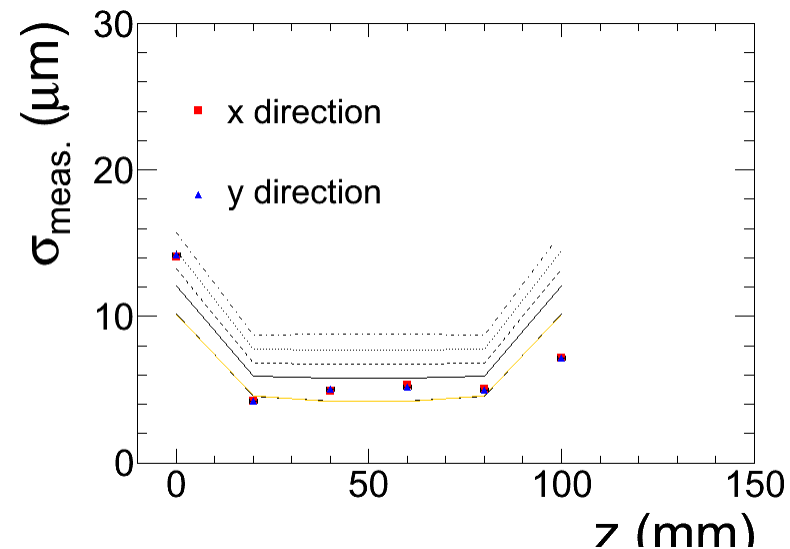
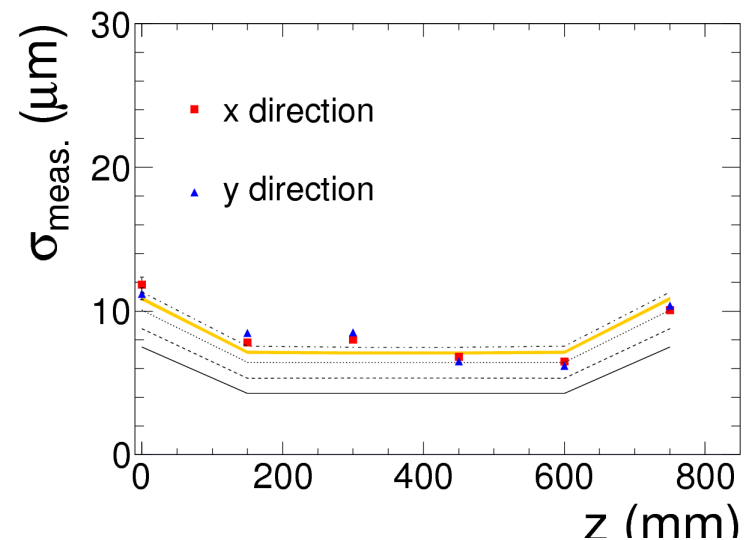
## ➤ Resolution depends on:

- beam energy (1 to 6 GeV)
- sensor distance (20 to 150 mm)

→ suffers greatly from multiple scattering

## ➤ First results – 2 GeV:

- $\sigma \sim 8 \mu\text{m}$  at 150 mm sensor distance
- $\sigma \sim 5 \mu\text{m}$  at 20 mm sensor distance



## > CMS Phase-II upgrade requires a new silicon tracker

- Sensors to withstand higher radiation dose → investigate new materials and layouts
- Cope with increased occupancy → improve granularity
- New modules, ROCs, cooling, contribute to the Level-1 trigger, ...

## > Beam telescopes as a powerfull tool to test sensors

- Pin-point a particle track → evaluate *device under test* performance  
→ DESY beam telescopes & testbeam used by a variety of groups

## > TCAD simulations

- Powerful tool to see the inner workings of silicon sensors
- Unirradiated sensor measurements can be reproduced
- Ongoing search for a defect model to implement radiation damage



## ➤ EUTelescope software framework

- Group of processors to convert raw detector data into particle tracks
- Actively maintained and supported at DESY

<http://eutelescope.desy.de>

